Abstract

A semiconductor processing system, wherein a carrying base table 30 is installed in a carrying mechanism 26 for carrying a processed substrate W to a processing device, first and second holing arms 32A and 32B are slidably installed parallel with each other on the carrying base table 30, and the first and second support arms 32A and 32B having first and second holding surfaces 33A and 33B for holding the processed substrate W are substantially positioned on the same plate and operated so that the first and second holding surfaces 33A and 33B can be projected in the same direction relative to the carrying base table 30.